

In re Appln. of VERMEERSCH et al.  
Application No. 10/811,469

#### CLAIM AMENDMENTS

1. (Currently Amended) A positive working heat-sensitive lithographic printing plate precursor comprising a support having a hydrophilic surface and a coating, provided on the hydrophilic surface, said coating comprising:

- an infrared light absorbing agent,
- an oleophilic resin soluble in an aqueous alkaline developer,
- a developer resistance means and
- spacer particles,

~~characterised in that~~ wherein said spacer particles comprise cross-linked polysiloxane and have an average particle size is between 0.6  $\mu\text{m}$  and 15  $\mu\text{m}$ .

2. (Original) A positive working heat-sensitive lithographic printing plate precursor according to claim 1 wherein said particle size is between 1  $\mu\text{m}$  and 15  $\mu\text{m}$ .

3. (Original) A positive working heat-sensitive lithographic printing plate precursor according to claim 1 wherein said cross-linked polysiloxane is a cross-linked polyalkylsiloxane.

4. (Original) A positive working heat-sensitive lithographic printing plate precursor according to claim 1 wherein said coating has a layer thickness comprised between 0.6  $\text{g}/\text{m}^2$  and 2.8  $\text{g}/\text{m}^2$ .

5. (Original) A positive working heat-sensitive lithographic printing plate precursor according to claim 1 wherein said coating comprises at least two layers and wherein said spacer particles are present in at least one of the layers of the coating.

6. (Original) A positive working heat-sensitive lithographic printing plate precursor according to claim 1 wherein the amount of said particles in the coating is between 5 and 200  $\text{mg}/\text{m}^2$ .

7. (Original) A positive working heat-sensitive lithographic printing plate precursor according to claim 1 wherein said developer resistance means is a polymer comprising siloxane or perfluoroalkyl units.

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8. (Original) A stack comprising a plurality of positive working heat-sensitive lithographic printing plate precursors, according to claim 1, wherein adjacent plate precursors are separated by an interleave.

9. (Original) A package comprising a stack according to claim 8.

10. (Currently Amended) Use of cross-linked polysiloxane spacer particles, having an average particle size larger than 0.6  $\mu\text{m}$ , in the coating of a positive working heat-sensitive lithographic printing plate precursor, said coating, provided on the hydrophilic surface, further comprising:

- an infrared light absorbing agent,
- an oleophilic resin soluble in an aqueous alkaline developer and
- a developer resistance means,

characterised in that wherein said spacer particles comprise cross-linked polysiloxane and have an average particle size larger than 0.6  $\mu\text{m}$ , ~~for improving~~ and improve the scuff-mark resistance of the coating.

11. (New) A method for improving the scuff-mark resistance of a positive working heat-sensitive lithographic printing plate precursor, the precursor comprising a support which includes a hydrophilic surface and a coating provided on the hydrophilic surface, the method comprising providing a support and hydrophilic surface, preparing a coating comprising: an infrared light absorbing agent, an oleophilic resin soluble in an aqueous alkaline developer, a developer resistance means, and spacer particles, wherein the spacer particles comprise cross-linked polysiloxane and have an average particle size larger than 0.6 $\mu\text{m}$ , and applying the coating onto the hydrophilic surface.